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	International Search Report dated 11/13/03 for international patent application no. PCTUS02/02921, filed on February 1, 2002.					

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1	FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASMEX.291A	APPLICATION NO. 10/074,583
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SHEET 1 OF 1 U.S. DEPARTMENT OF COMMERCE ATTY, DOCKET NO. APPLICATION NO. **FORM PTO-1449** PATENT AND TRADEMARK OFFICE ASMEX.291A 10/074,563 INFORMATION DISCLOSURE STATEMENT BY APPLICANT OIPE APPLICANT Todd et al. SEVERAL SHEETS IF NECESSARY) FILING DATE **GROUP** February 11, 2002 **U.S. PATENT DOCUMENTS** RADEMARK **EXAMINER** DOCUMENT NUMBER DATE NAME CLASS SUBCLASS FILING DATE INITIAL (IF APPROPRIATE) 6,159,828 12/12/00 Ping et al. 438 486 6,171,662 B1 01/09/01 Nakao 427 595 6,197,669 B1 03/06/01 Twu et al. 438 585 MAN **FOREIGN PATENT DOCUMENTS EXAMINER** DOCUMENT NUMBER DATE COUNTRY CLASS SUBCLASS TRANSLATION INITIAL YES NO **EXAMINER** OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.) INITIAL S:\DOCS\JOM\JOM-4096.DOC:112102

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE ATTY. DOCKET NO. ASMEX.291A

APPLICATION NO. 10/074,563

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

APPLICANT Todd et al.

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